

Docket No. 00884.386US1



**Clean Version of Pending Claims**

INTERCONNECT  
Applicant: Erik W. Jensen  
Serial No.: 09/740,103

Client Ref. No. P10648

RECEIVED  
NOV - 1 2002  
TC 800 MAIL ROOM

- 
2. An interconnect comprising:  
a substrate;  
a pad formed on the substrate; and  
at least two vias coupled to the pad, wherein only one of the at least two vias is formed substantially beneath the pad.
- C<sup>1</sup> 3. The interconnect of claim 2, wherein at least one of the at least two vias is coupled to the pad by a conductive segment having a first end having a first width and a second end having a second width, the first end being connected to the at least one of the at least two vias and the second end being connected to the pad, and the first width being less than the second width.
4. The interconnect of claim 2, wherein the pad has at least five substantially straight edges and the at least two vias comprise three vias and only two of the three vias are coupled to the substantially straight edges.
5. The interconnect of claim 4, wherein at least one of the only two of the three vias coupled to the substantially straight edges is coupled to one of the substantially straight edges through a tapered conductive segment.
- 
21. The interconnect of claim 2, wherein the pad comprises copper.
- C<sup>2</sup> 22. The interconnect of claim 21, wherein the at least two vias comprise cylindrical conductors.

23. An interconnect comprising:  
a substrate;  
a pad formed on the substrate; and  
at least three vias coupled to the pad, wherein only one of the at least three vias is formed substantially beneath the pad.
24. The interconnect of claim 23, wherein at least one of the at least three vias is coupled to the pad by a tapered conductive segment.
25. The interconnect of claim 24, wherein the tapered conductive segment comprises copper.
26. The interconnect of claim 25, wherein the tapered conductive segment comprises a hyperbolic taper.
27. The interconnect of claim 26, wherein the pad comprises gold.
28. The interconnect of claim 27, wherein each of the at least two vias comprise triangular conductors.
29. (Amended) An interconnect comprising:  
a substrate;  
a pad formed on the substrate; and  
at least four vias coupled to the pad, wherein only one of the at least four vias is formed substantially beneath the pad.

Control  
C2

30. The interconnect of claim 29, wherein at least three of the at least four vias is coupled to the pad by a tapered conductive segment.

31. The interconnect of claim 30, wherein the tapered conductive segment comprises aluminum.

32. The interconnect of claim 31, wherein the tapered conductive segment includes an exponential taper.

33. The interconnect of claim 32, wherein the pad comprises tungsten.

34. The interconnect of claim 33, wherein each of the at least four vias comprise square conductors.

35. An interconnect comprising:  
a substrate;  
a pad formed on the substrate; and  
at least five vias coupled to the pad, wherein only one of the at least five vias is formed substantially beneath the pad.

36. The interconnect of claim 35, wherein the pad comprises silver.

37. (Amended) The interconnect of claim 36, wherein the at least five vias comprise hexagonal conductors.

---